Electronic supplementary information

Heterojunction of nanostructured α-Fe₂O₃/CuO for enhancement of photoelectrochemical water splitting

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Fig. S1. XRD pattern of α -Fe₂O₃ and α -Fe₂O₃/CuO films indicating the peak shifts of (104) and (110) planes. Note: the * symbol represent the XRD peaks of FTO substrates.



Fig. S2. Raman spectra of α -Fe₂O₃, CuO and α -Fe₂O₃/CuO films showing the difference in peaks intensities.



Fig. S3. Histogram of particle size distribution for (a) α-Fe₂O₃, (b) α-Fe₂O₃/CuO and (c) CuO films.



Fig. S4. EDS analysis carried out on the surface of α -Fe₂O₃/CuO films.



Fig. S5. Photocurrent density of (a) α -Fe₂O₃ and (b) α -Fe₂O₃/CuO showing the results for measurements done in dark and under illumination in each.



Fig. S6. Bode Plots for α -Fe₂O₃ and α -Fe₂O₃/CuO films of (a) Log frequency (Hz) vs. modulus of impedance |Z| and (b) Log frequency (Hz) vs. phase (°). Both plots agree with the Nyquist plots confirming a reduction of charge transfer resistance for α -Fe₂O₃/CuO over α -Fe₂O₃ photoanodes. Fig. S4(a) revealed significant drop in absolute impedance for α -Fe₂O₃/CuO at lower frequencies relative to α -Fe₂O₃ indicating reduction of charge transfer resistance. Similarly, Fig. S4(b) shows a phase peak shift to a lower frequency also depicting a drop of charge transfer resistance.



Fig. S7. EIS Nyquist plots for $\alpha \alpha$ -Fe₂O₃, α -Fe₂O₃/CuO and α -Fe₂O₃/CuO (using 15% methanol as SR in the electrolyte) samples: the dotted coloured lines shows the raw experimental data acquired using VersaSTAT 3F potentiostat from Princeton Applied Research while the grey solid lines present the respective fitted curves of the films obtained with ZView software from Scribner Associates.